



## **AVIOR M-300** Vacuum coating system for high-performance optical filters



Dr. Antun Peić, M.Sc. Lukas Hell

## Introduction

### Part I: The AVIOR M-300 Platform - Ultra high-precision Coating on up to 300 mm

- AVIOR M-300 Overview
- Main Configuration
- Configuration Options
- Flexible Turntable Design for Universal Substrate Loading
- Run-to-Run Stability
- AVIOR M-300 Key Facts and Features

### Part II: AVIOR M-300 - Process Technology

- a-Si:H/SiO<sub>2</sub> NIR Bandpass Filter
- High-performance NIR Bandpass Filter: X39 Filter
- SOLAYER “Zero Bow” Technology: X41 Filter
- CWDM Filter Development



# GLOBAL LOCATIONS

With our HQ near Frankfurt, a research and development site near Dresden and subsidiaries in the USA, China, Taiwan and Singapore, SOLAYER is globally positioned to serve customers all over the world.



- Located near Frankfurt within the Material Valley
- D&E of vacuum deposition equipment & components

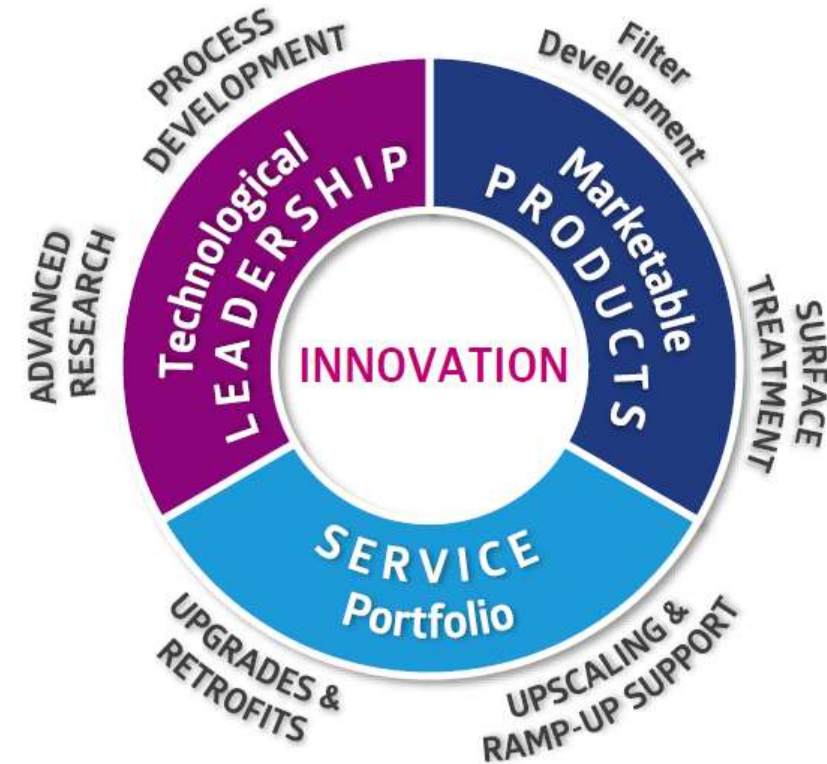
- HQ near Dresden in Silicon Saxony
- R&D for precision thin-films and filter technologies



## MISSION

“With a clear focus on the development & applications of the innovative thin film technologies - We support our customers in a highly competitive market”

- **Technological Leadership**  
Transforming innovation into processes and products
- **Marketable Products**  
Most versatile product platform enables ultra high-precision optical coatings with extraordinary film quality combined with filter and process development that highly benefit customers
- **Service Portfolio**  
Offering specialized support to help customers succeed in a very competitive market with upgrade & retrofits, process development, product development and thin film services



# MARKET ACTIVITIES & COMPETENCES

## TECHNOLOGY EXPERTISE



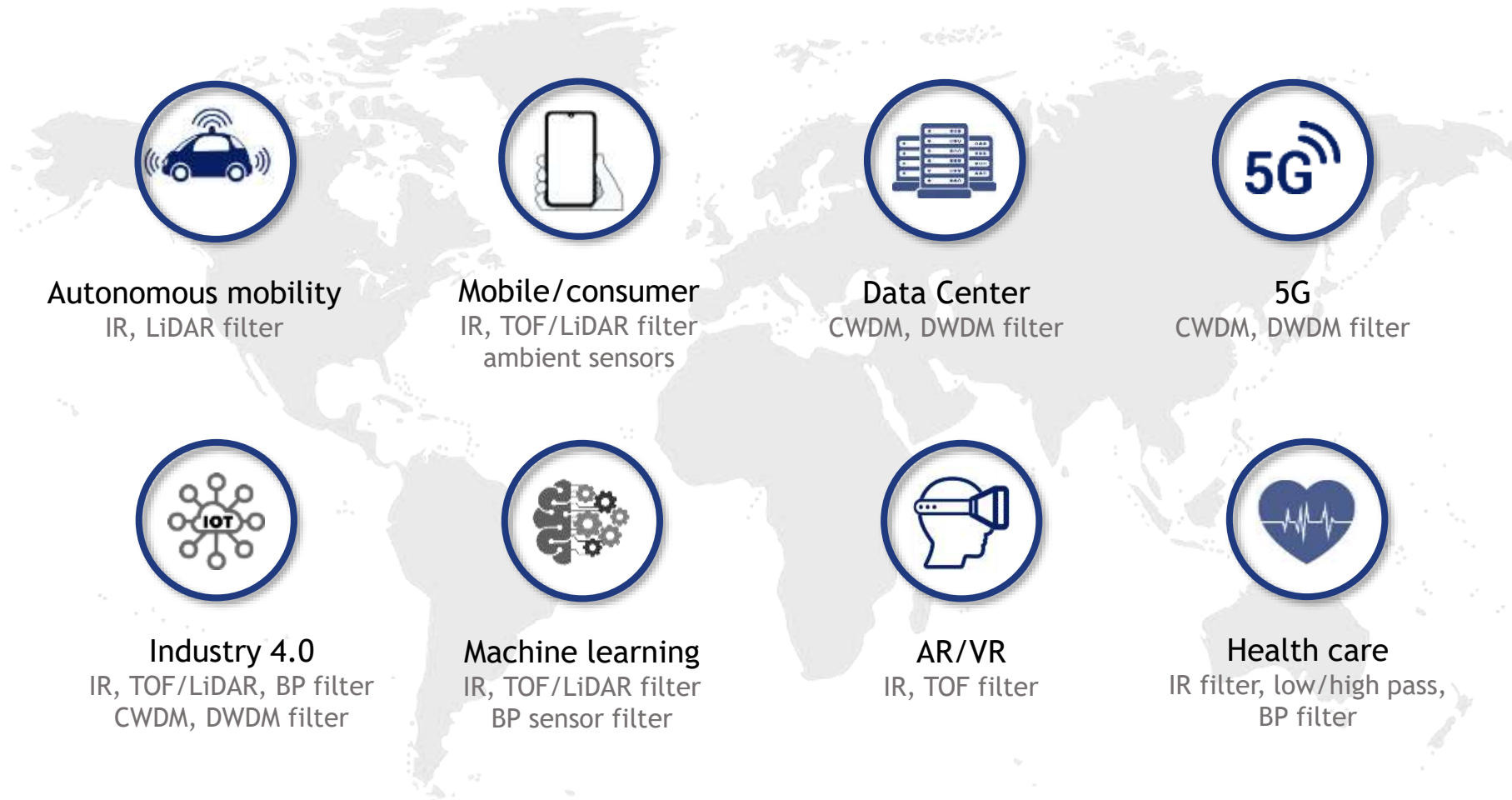
## EQUIPMENT & TOOLS



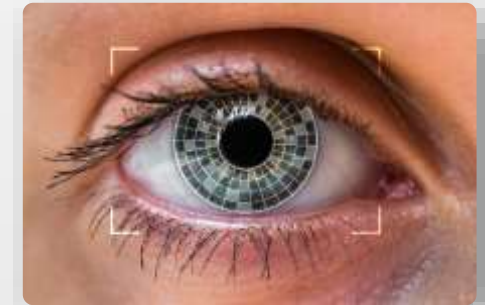
## CUSTOMER SUPPORT

## MARKET FOCUS

# DRIVEN BY PHOTONICS MEGATRENDS DEMAND



Source: YOLE Development, Gartner, PWC



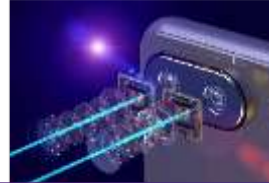
# HIGH-PRECISION OPTICAL COATING PLATFORMS



ALIO TH



AVIO R



ALASCO



## HIGH THROUGHPUT INLINE COATING

## ULTRA HIGH-PRECISION COATING

## FLEXIBLE & MULTI-FUNCTIONAL COATING



### DETAILED PROCESS STEPS

LOAD LOCK

PRE-TREATMENT

PROCESS CHAMBER

POST-TREATMENT



SOLAYER Confidential





## Part I: The AVIOR M-300 Platform - Ultra high-precision Coating on up to 300 mm

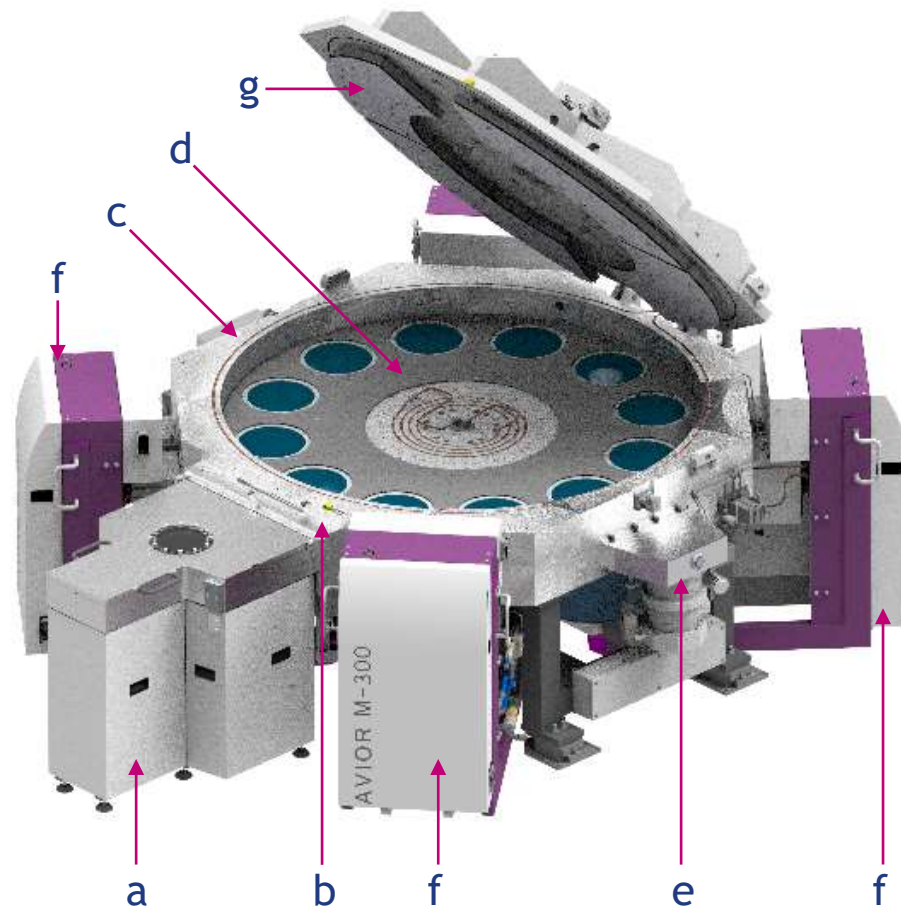
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- AVIOR M-300 Key Facts and Features

# AVIOR M-300 HIGH-PRECISION COATING ON 300 MM



- Flexible and modular platform
- Excellent process stability
- High-precision thin-film coatings
- Outstanding productivity
- Ready for future demands

# AVIOR M-300 MAIN COMPONENTS



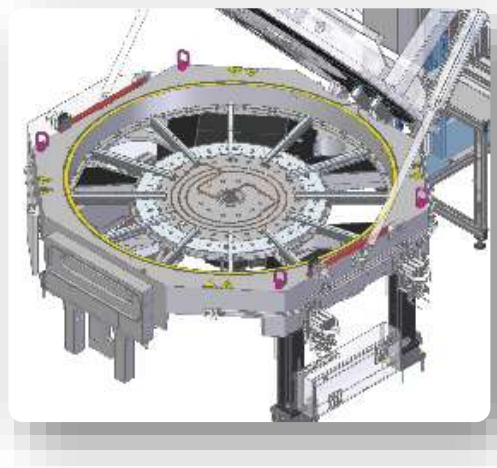
- a) Load/unload handling  
(automatic or manual)
- b) Gate valve
- c) Process chamber
- d) Turn table  
(12 x Ø 300 or 24 x Ø 200 or 48 x Ø 150)
- e) Plasma source # 1-2
- f) Sputter magnetrons # 1-4  
(dual rotary magnetrons)
- g) Substrate heating (option)

# AVIOR M-300 OPTIONS

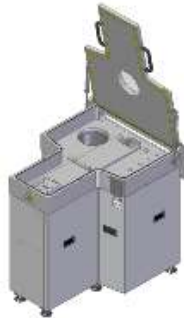
## Base System

## Loading

## Process Options



- Modular design
- Future-proof
- Upgradable



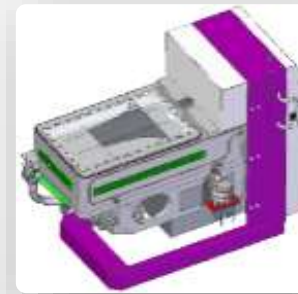
**Semi-manual single loading**  
Automatic turntable loading  
Load/unload cycle ~ 105 min

**Segment single batch stacker**

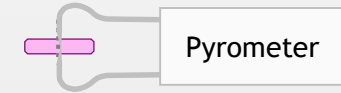
Automatic turntable loading  
Load/unload cycle ~ 38 min



**Customized Solutions**  
Various formats & handling concepts

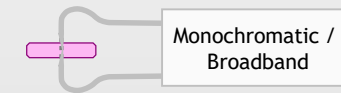


Sputter #1-4



Pyrometer

Highspeed temperature



Monochromatic /  
Broadband

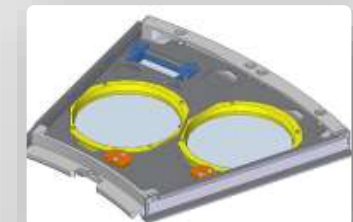
Optical monitoring



Plasma #1-2



Gas Supply  $H_2$   $O_2$   $N_2$   
Top/bottom heater



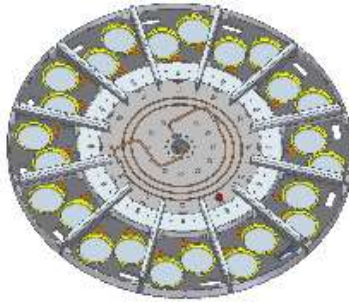
Witness glass exchange

# AVIOR M-300 UNIVERSAL CONFIGURATION

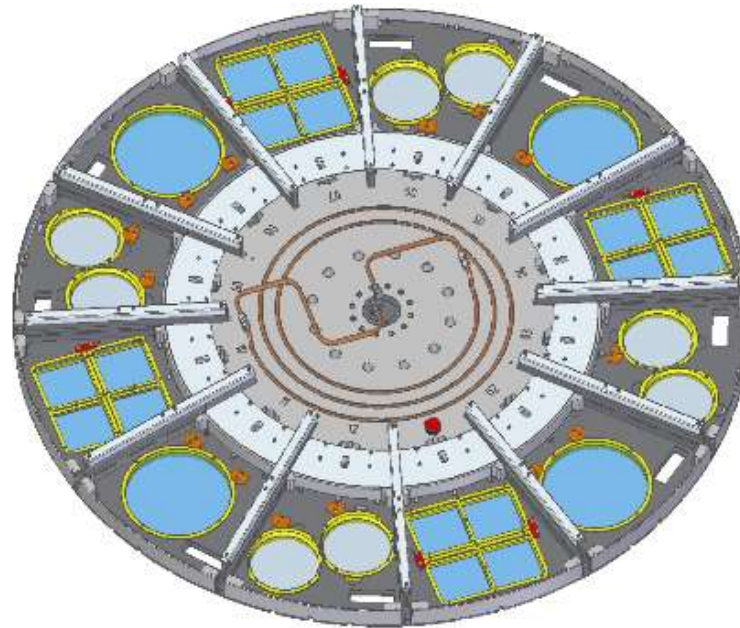
12 x 300 mm



24 x 200 mm



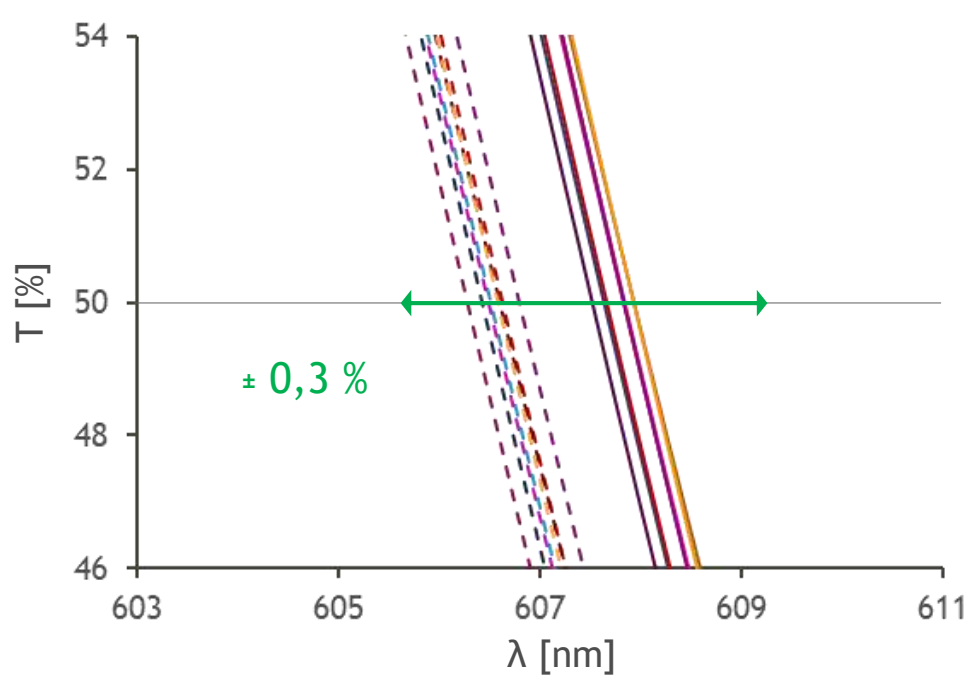
48 x 150 mm



Various sizes and shapes possible

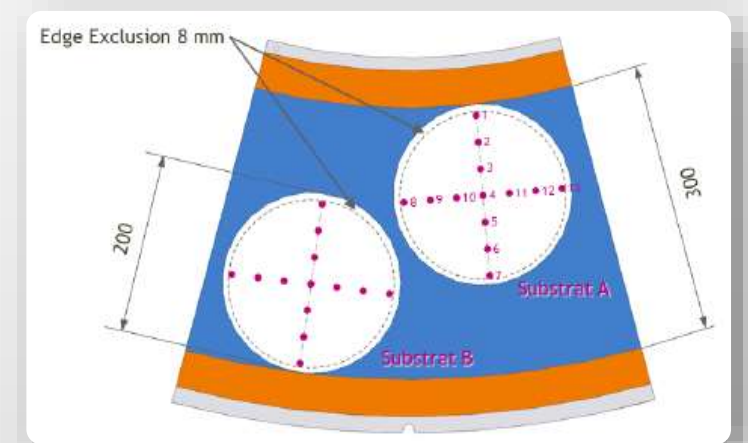
- Universal substrate loading
- One turntable covers all substrate sizes
- No mechanical modification needed
- Economic equipment utilization

# AVIOR M-300 RUN-2-RUN



- Run-A, Carrier 1; Pos A-4
- Run-A, Carrier 1; Pos B-4
- Run-A, Carrier 6; Pos A-4
- Run-A, Carrier 6; Pos B-4
- Run-B, Carrier 1; Pos A-4
- Run-B, Carrier 1; Pos B-4
- Run-B, Carrier 6; Pos A-4
- Run-B, Carrier 6; Pos B-4
- Run-C, Carrier 1; Pos A-4
- Run-C, Carrier 1; Pos B-4
- Run-C, Carrier 6; Pos A-4
- Run-C, Carrier 6; Pos B-4
- Run-D, Carrier 1; Pos A-4
- Run-D, Carrier 1; Pos B-4
- Run-D, Carrier 6; Pos A-4
- Run-D, Carrier 6; Pos B-4

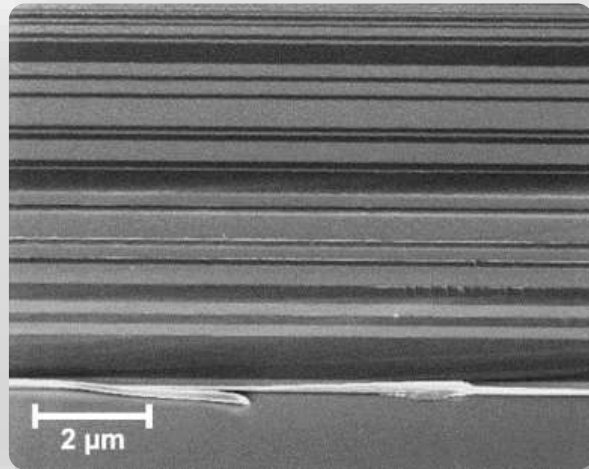
□ Run A-D, Carrier 1 & 6, Pos A4 & B4



- 26L low-pass
- $\text{SiO}_2/\text{Nb}_2\text{O}_5$
- 2.488  $\mu\text{m}$
- Time controlled

# AVIOR M-300 KEY FACTS

## Film Quality



- Uniformity  $\leq \pm 0.2 \%$
- Dense, stable, low defect  
→ shift-free films
- In-situ process automation  
& optical monitoring

## Process



- Compound assisted reactive sputtering (CARS)
- Sputter-Up configuration
- Dual-Rotatable Cathode arrangement

## Productivity



- Fully automated loading system
- High deposition rates up to 0.6 nm/s (~2 μm/h)
- Fast process adaptations, no test runs needed

## Flexibility



- Wide variety of film materials available
- Up to 4 materials with out any exchange
- Convertible substrate carrier for up to  $\varnothing 300$



## Part II: AVIOR M-300 - Process Technology

- a-Si:H/SiO<sub>2</sub> NIR Bandpass Filter
- High-performance NIR Bandpass Filter: X39 Filter
- SOLAYER “Zero Bow” Technology: X41 Filter
- CWDM Filter Development

## What products/processes can you achieve with the AVIOR M-300?

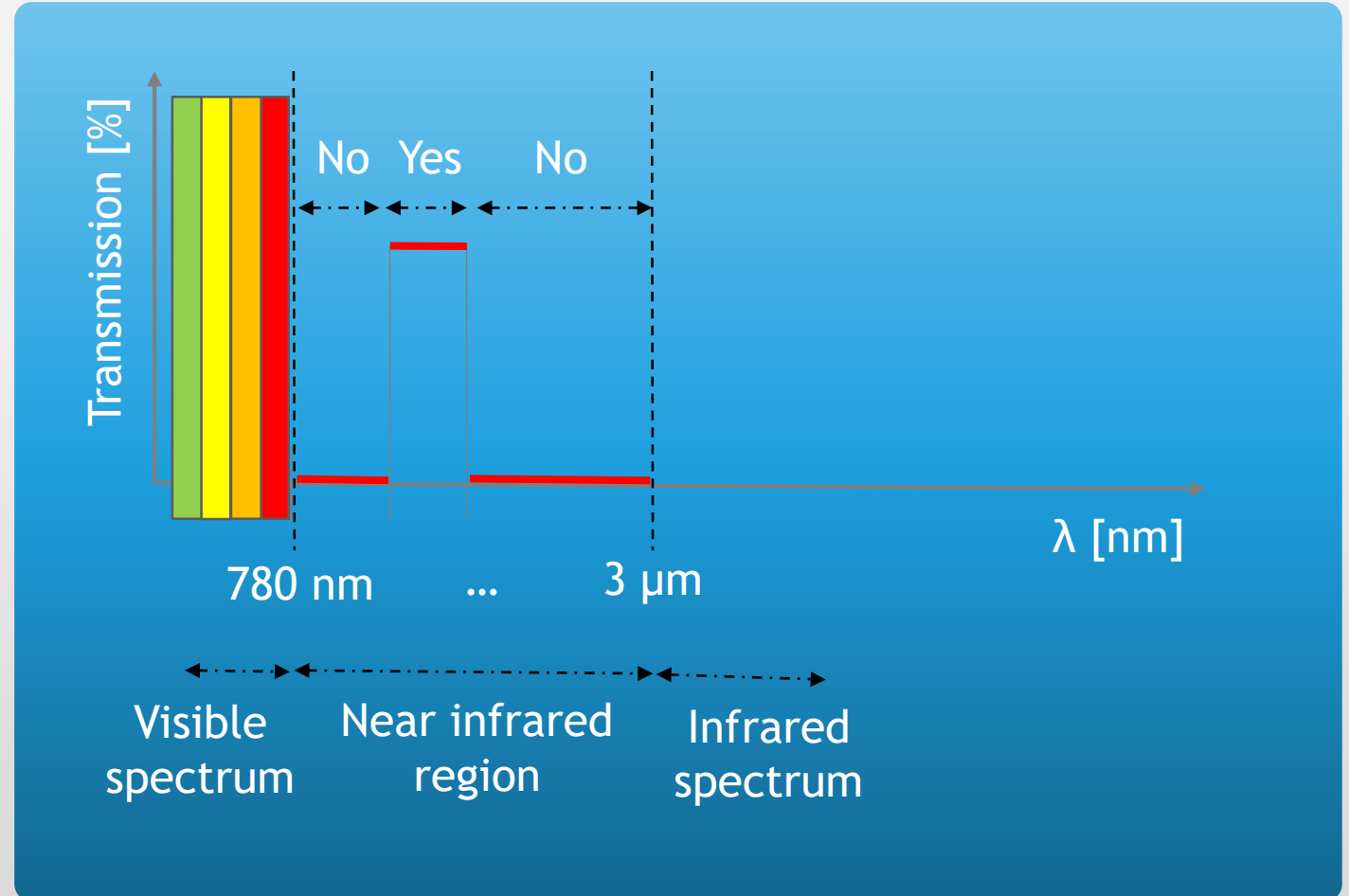
### NIR bandpass filter for many applications in the infrared wavelength region

- ❑ Key components for optical measurements, distance measurement applications or specific systems for gesture recognition
- ❑ The special characteristic of these filters allows:
  - Accurate distance measurements at low light intensity conditions
  - Measurements with higher sensitivity
  - Higher precision at normal signal light levels

### CWDM filter

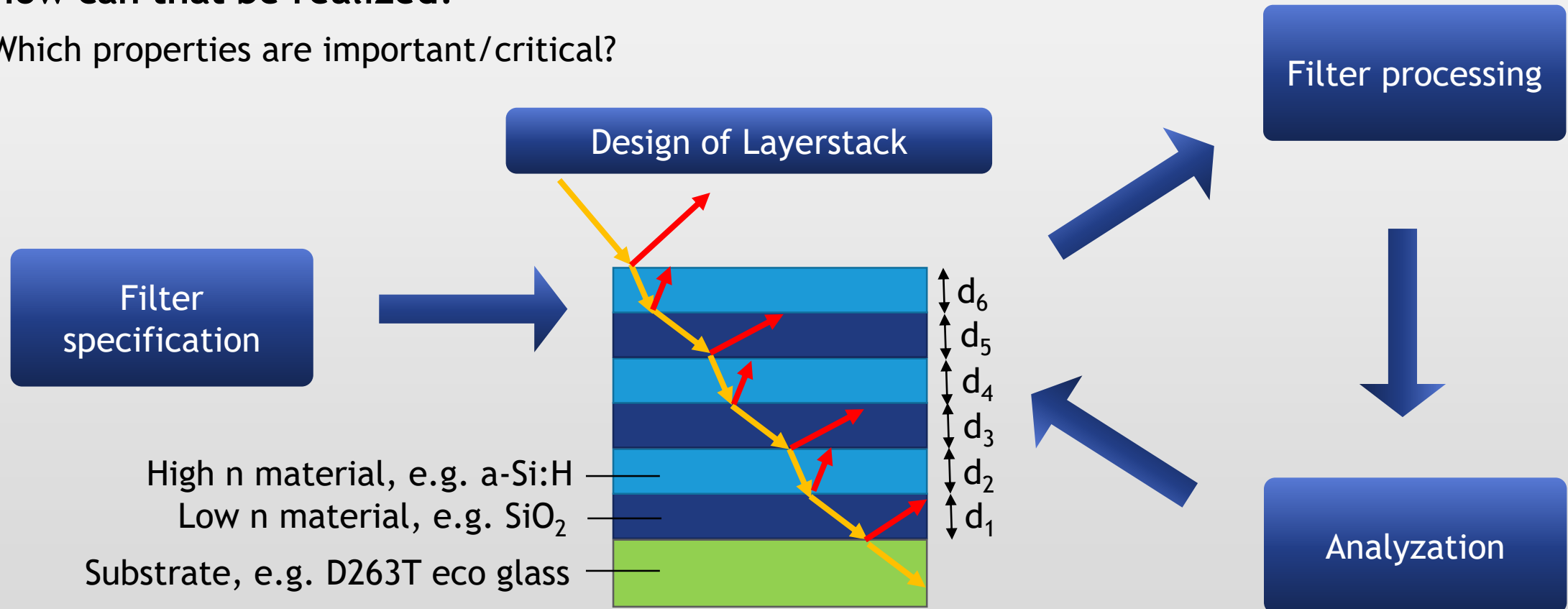
- ❑ Wavelength division multiplexers (WDM) are used to combine or separate optical signals with different wavelengths
- ❑ CWDM (C - Coarse) are multiplexers or demultiplexers for separating or merging signals with a channel spacing of 20 nm
- ❑ Applications: CWDM transmission systems, cable television networks, ... etc
- ❑ CWDM filter development is SOLAYERS' s intermediate step on the way to 5G capable filter solutions up to DWDM (D - Dense) with significantly smaller channel spacings

- What is a NIR bandpass filter?
- How can that be realized?
- Which properties are important/critical?



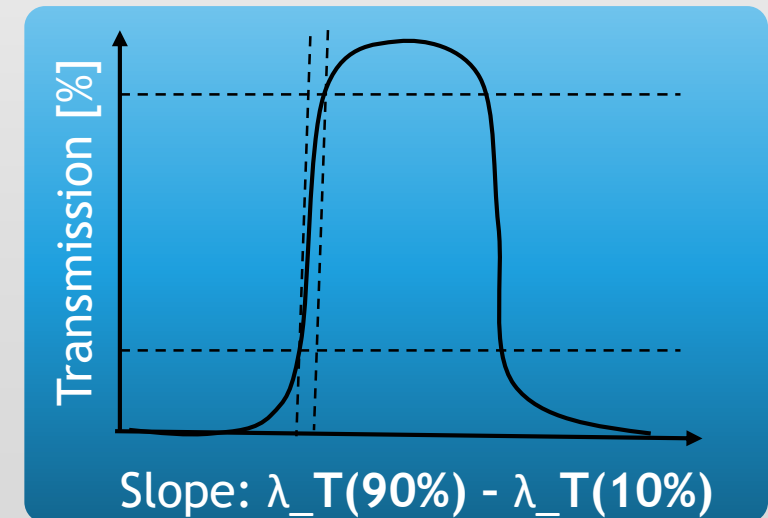
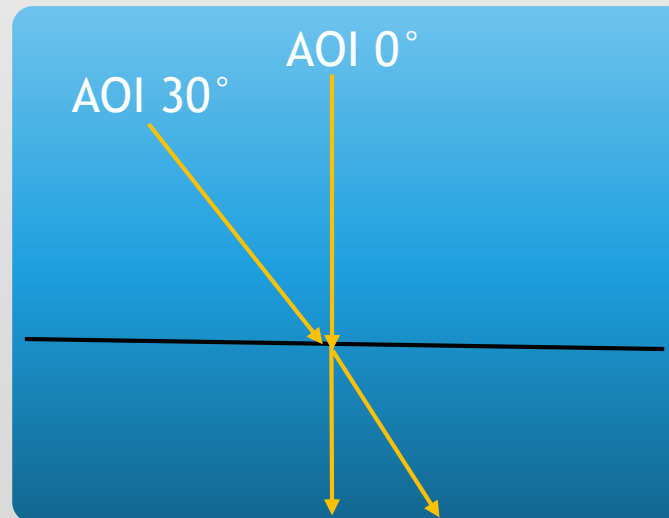
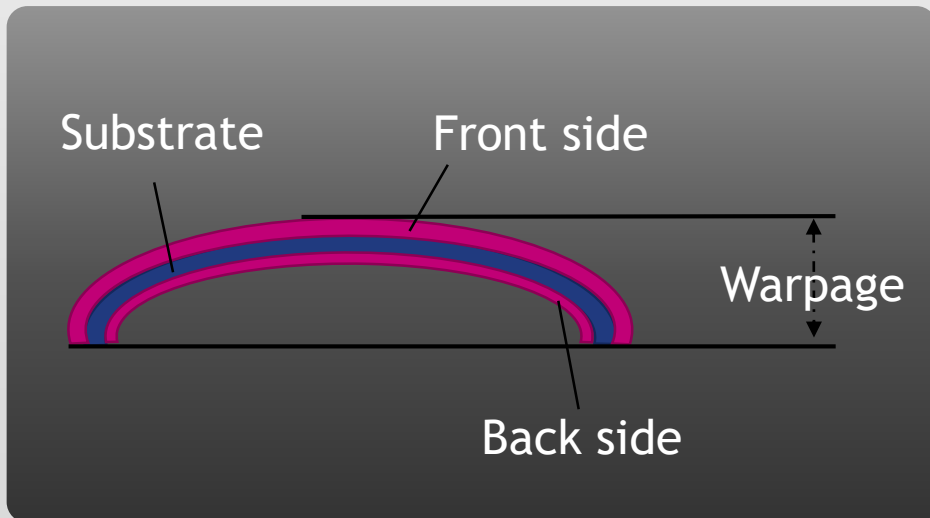
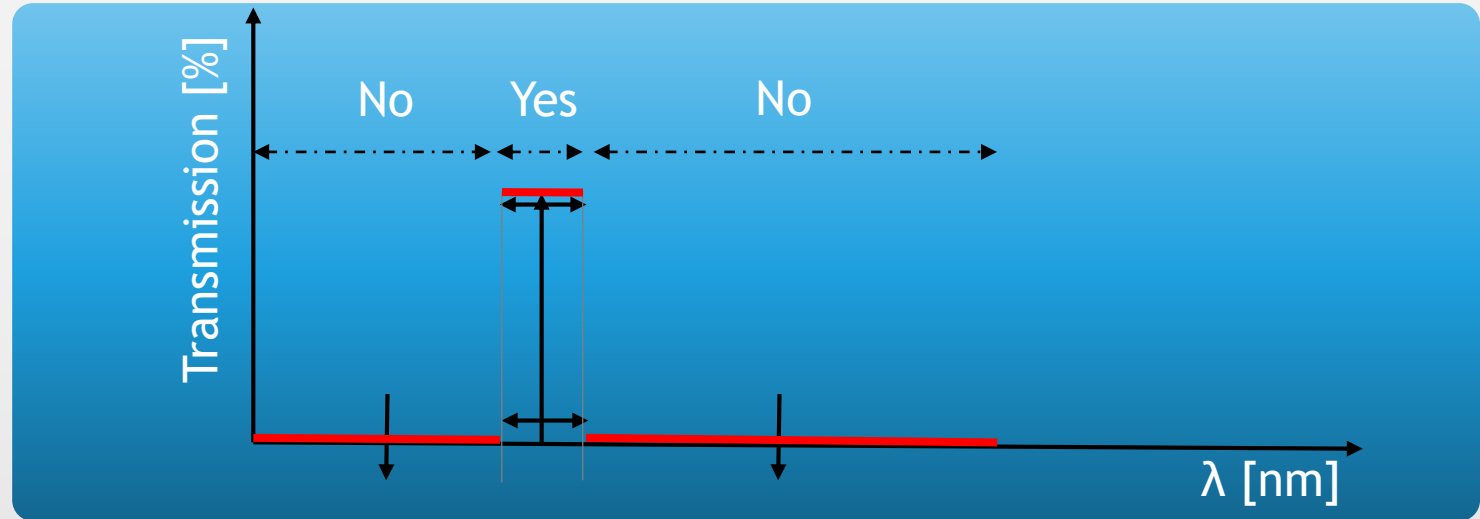
# A-Si:H NIR BANDPASS FILTER

- What is a NIR bandpass filter?
- **How can that be realized?**
- Which properties are important/critical?



# A-Si:H NIR BANDPASS FILTER

- What is a NIR bandpass filter?
- How can that be realized?
- **Which properties are important/critical?**

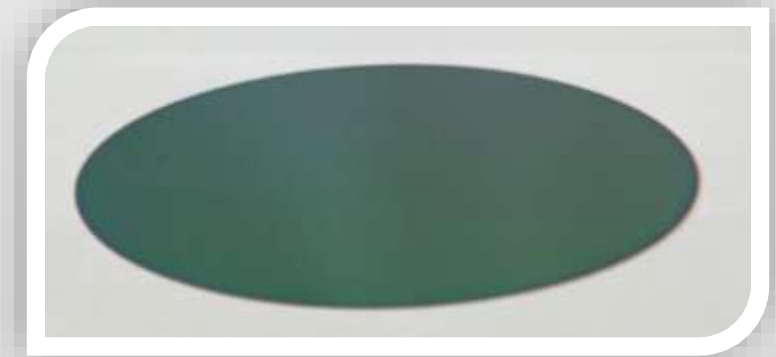


## Solutions with AVIOR M-300: X39 and X41 Technology

- 20-40 layer a-Si:H/SiO<sub>2</sub> filter systems
- Layerstack is designed with „OptiLayer“
- Deposition rates of nearly  $0.6 \frac{nm}{s}$  for a-Si:H and  $0.8 \frac{nm}{s}$  for SiO<sub>2</sub>
- Ø 200 mm glass substrates with 0.2 mm thickness
- Process stability: time controlled
- **X39 → High-performance NIR bandpass filter**
  - Standard NIR bandpass filter
  - High transmission values
- **X41 → „Zero Bow“ Technology**
  - Excellent blocking properties
  - Simplified and enabled post-processing, e.g. transport handling, waferbonding, ... etc.
  - Adjustable filter shape for high-end LiDAR applications



**SOLAYER X39 Technology**

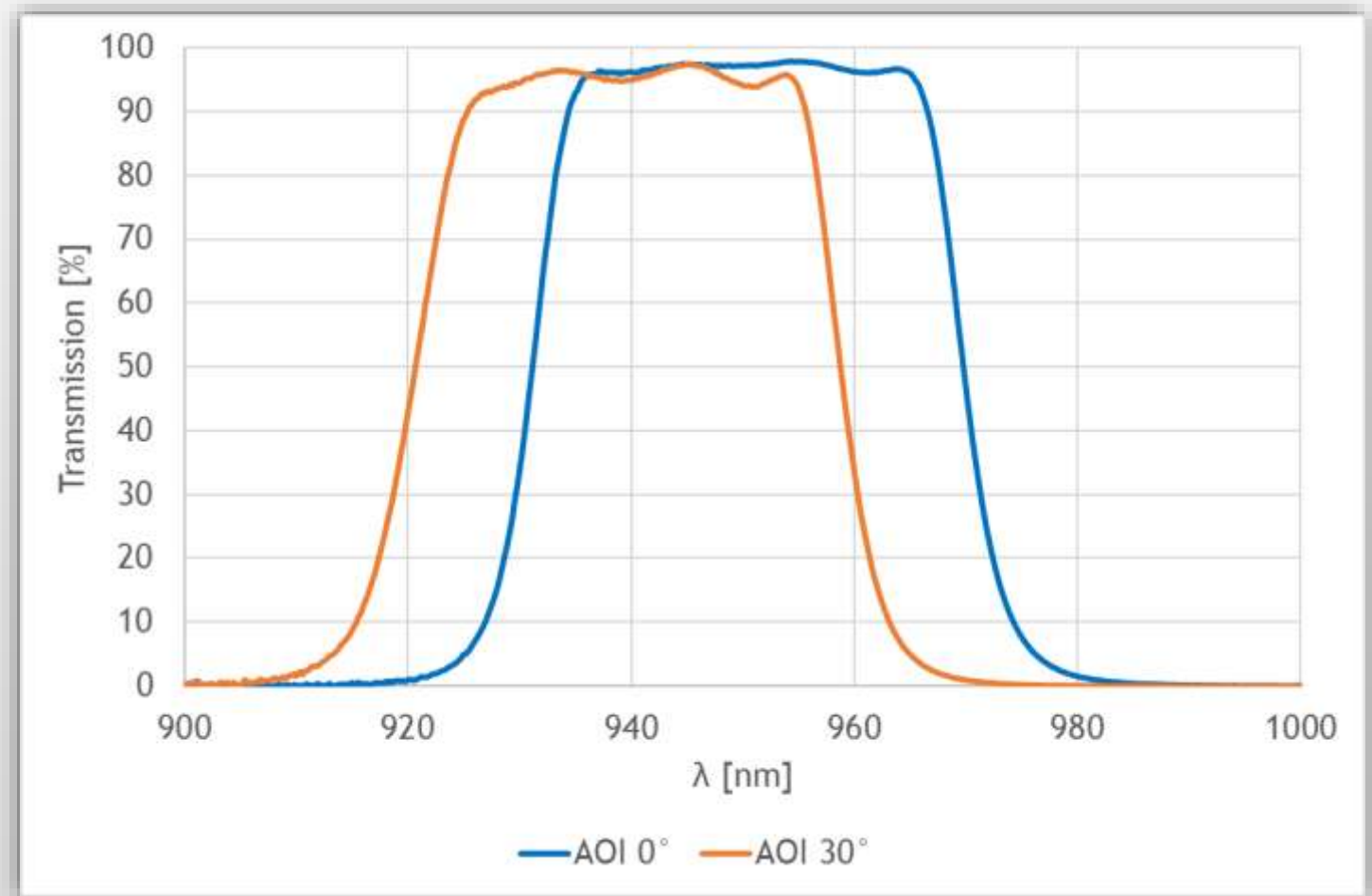


**SOLAYER „Zero Bow“ X41 Technology**

# A-Si:H NIR BANDPASS FILTER X39

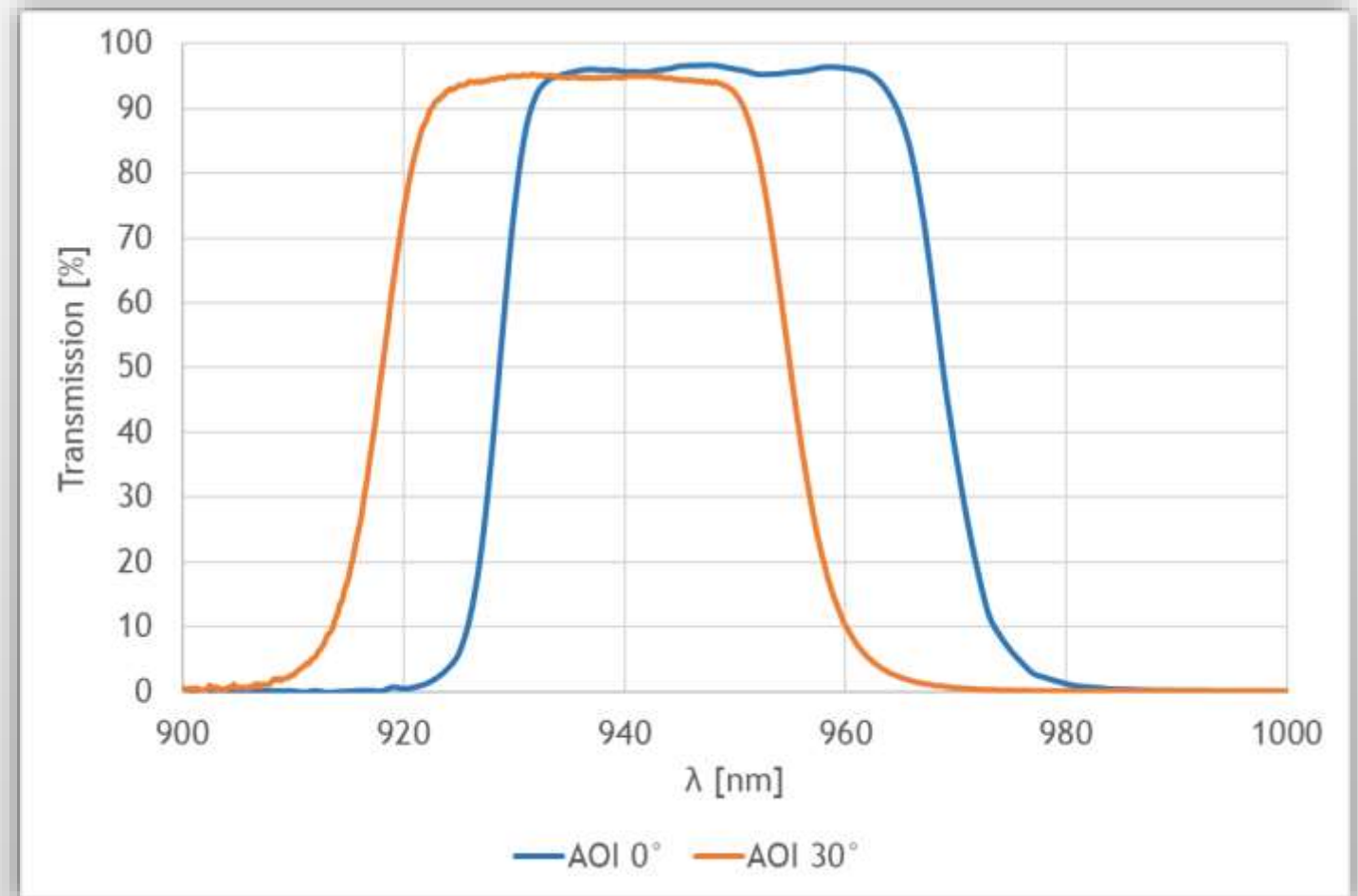
## □ Filter Performance

Central wavelength	950.5 nm
Bandpass length	32.15 nm
Transmittance in the bandpass	$T_{avg}$ in PB > 96.0 % $T_{min}$ in PB > 93.0 %
Blocking in cut off bands	OD > 5 avg (UV - 900 nm) OD > 5 avg (1000 - 1100 nm) OD > 4 abs (UV - 900 nm) OD > 3 abs (1000 - 1100 nm)
Angle of Incidence (AOI) - Shift	< 10.5 nm
Slope	< 9 nm
Substrate size	Ø 200 mm
Substrate thickness	0.2 mm
Warpage	< 11 mm

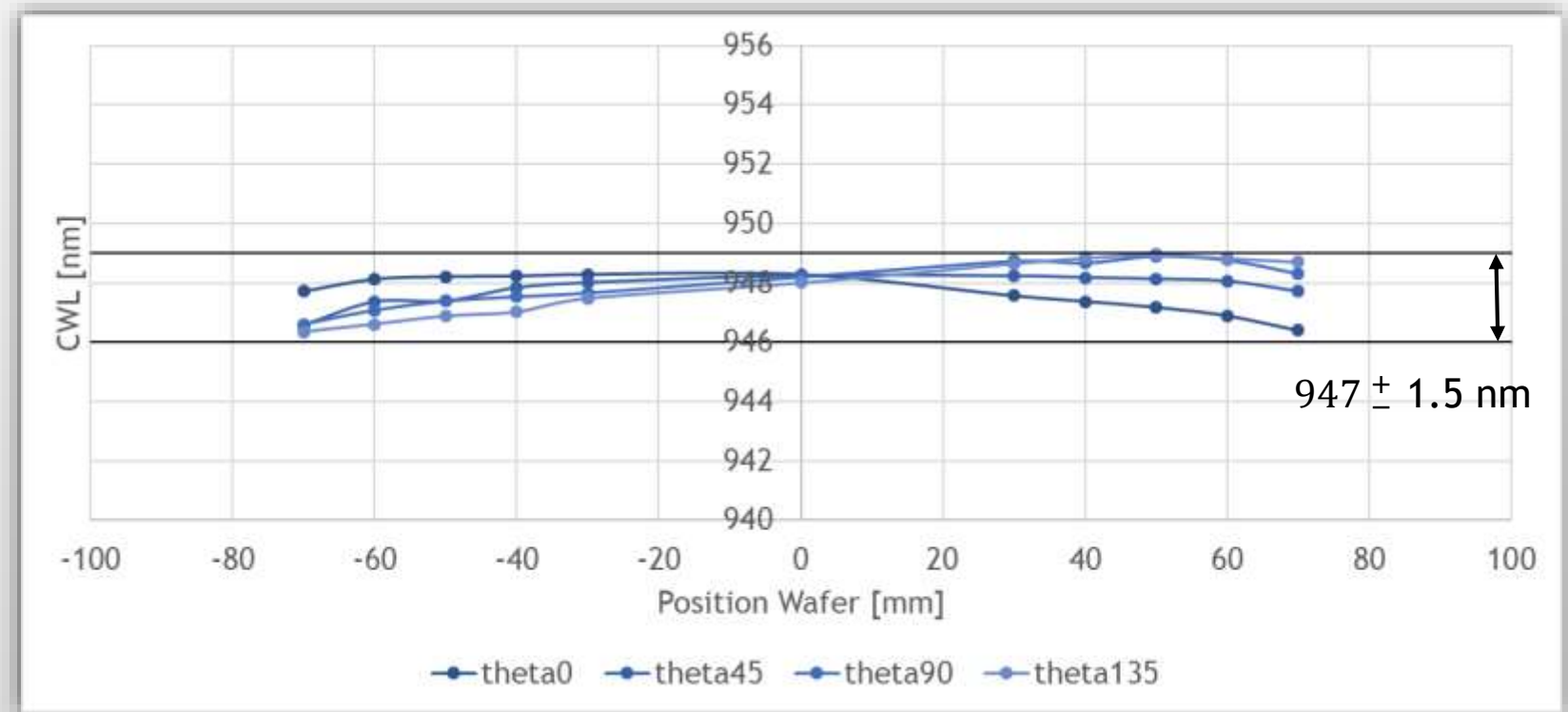
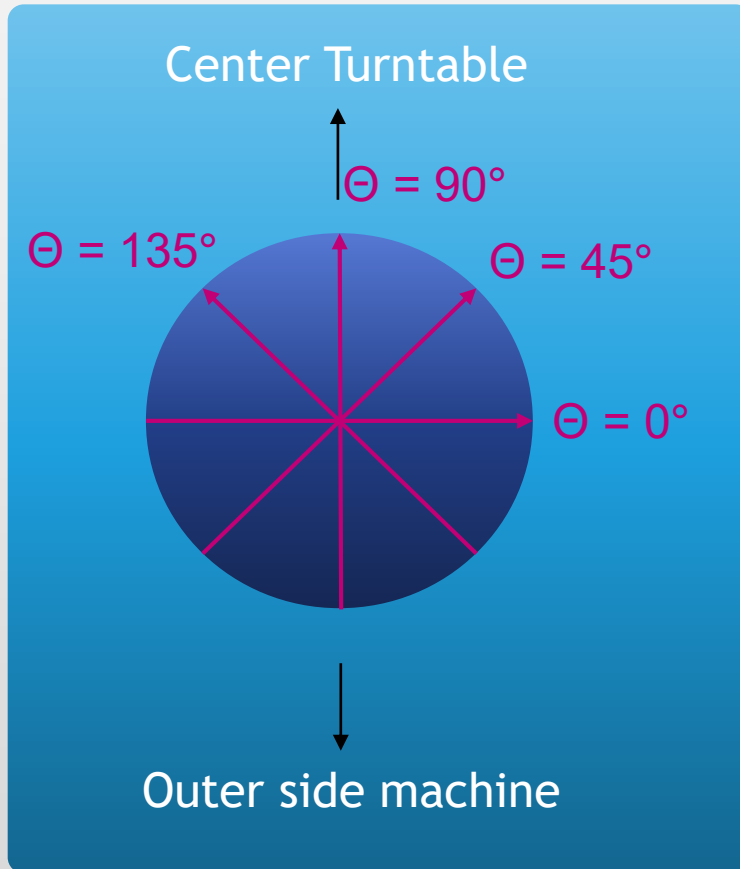


## Filter Performance

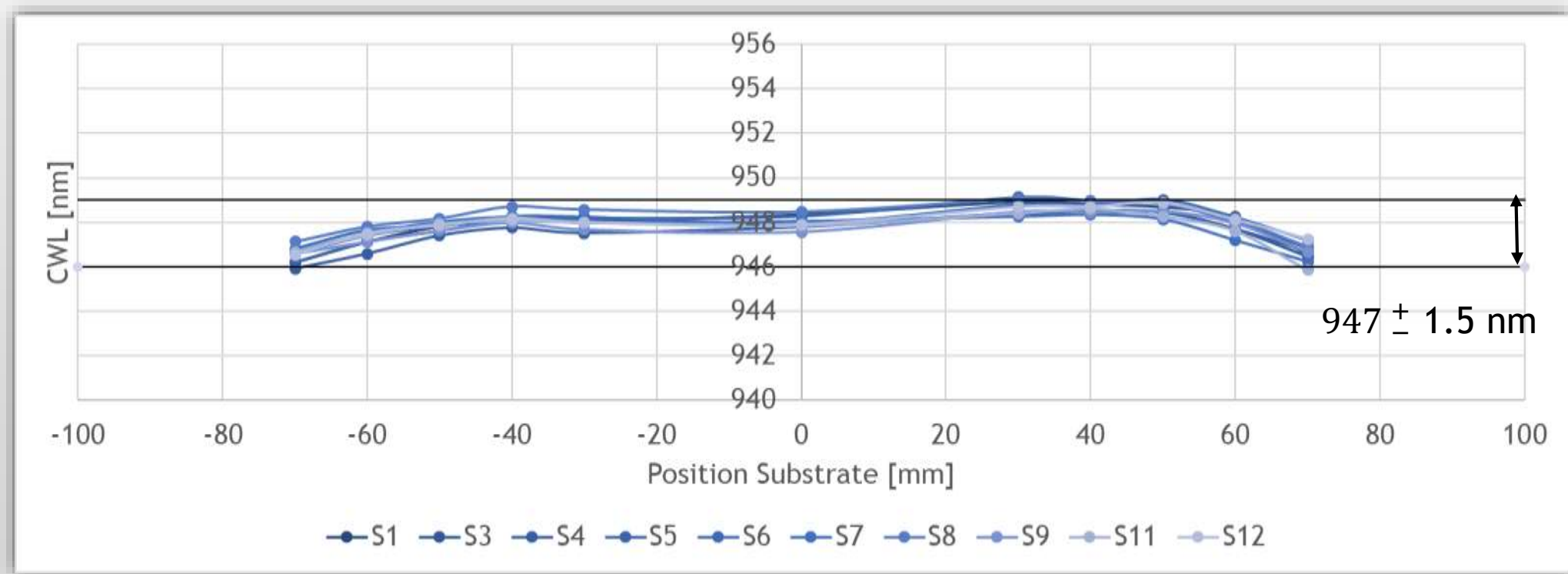
Central wavelength	948.2 nm
Bandpass length	32.90 nm
Transmittance in the bandpass	$T_{avg}$ in PB > 96.0 % $T_{min}$ in PB > 92.0 %
Blocking in cut off bands	OD > 5 avg (UV - 900 nm) OD > 5 avg (1000 - 1100 nm) OD > 4 abs (UV - 900 nm) OD > 4 abs (1000 - 1100 nm)
Angle of Incidence (AOI) - Shift	< 11 nm
Slope	< 9 nm
Substrate size	Ø 200 mm
Substrate thickness	0.2 mm
Warpage	0 mm



## □ Uniformity

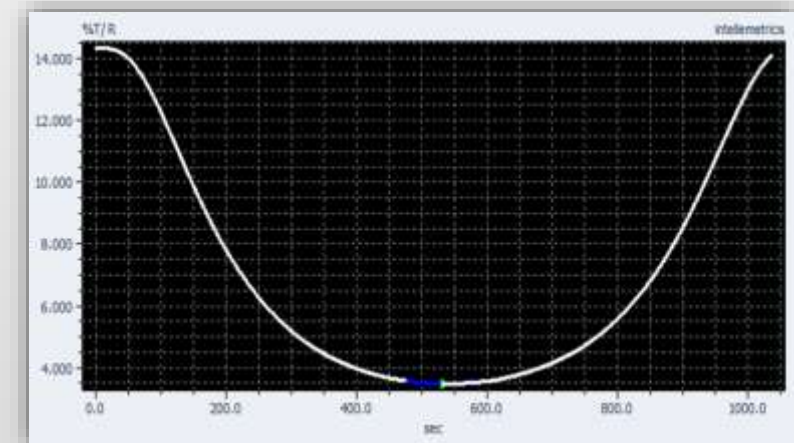


## Radial Uniformity Position to Position



## Basic parameters of CWDM process

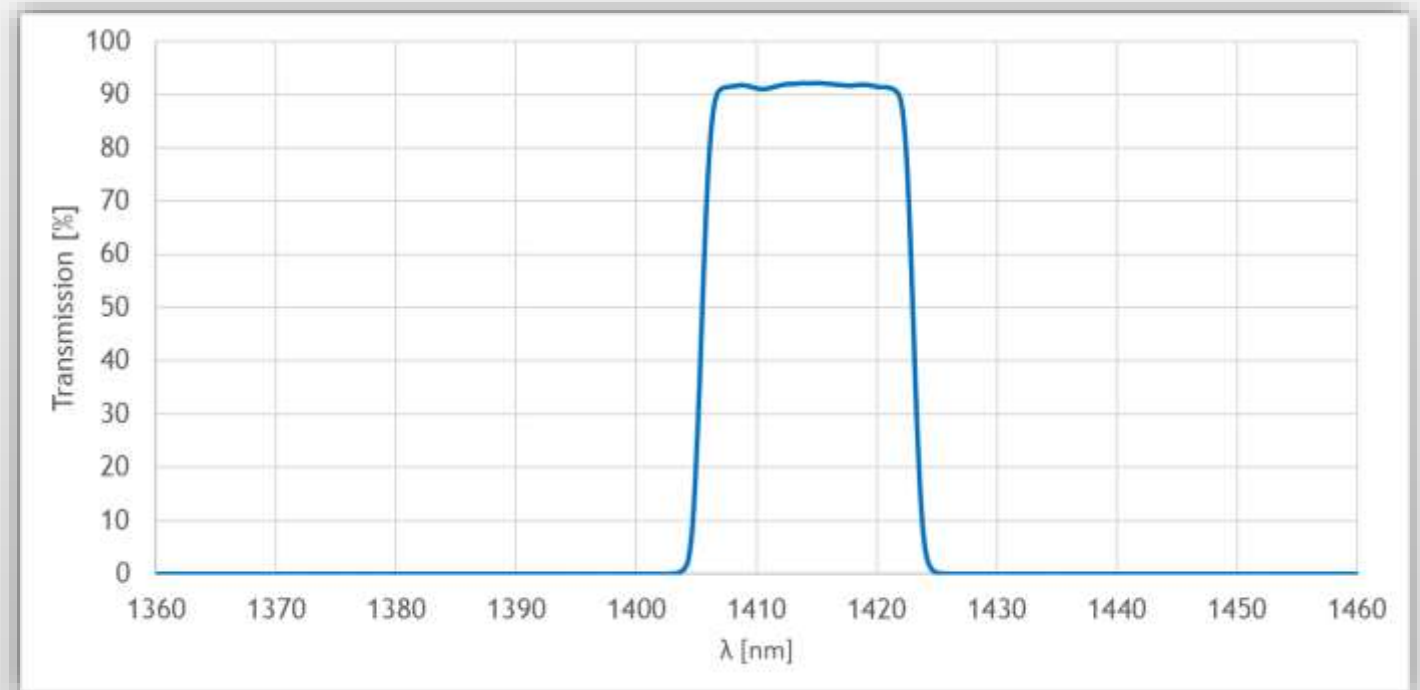
- 120-140 layer Ta<sub>2</sub>O<sub>5</sub>/SiO<sub>2</sub> filter system
- Layerstack is designed with „Macleod“
- Deposition rates of nearly  $0.7 \frac{nm}{s}$  for Ta<sub>2</sub>O<sub>5</sub> and  $0.6 \frac{nm}{s}$  for SiO<sub>2</sub>
- Ø 150 mm BK7 glass substrates with 10 mm thickness
- Process stability: Monochromatic Monitoring System (Intellemetrics)



## □ Filter Performance

Central wavelength	1414.2 nm
Max. Insertion Loss in Passband without backside AR	< 0.48 dB
Passband width @-0.25dB	15.37 nm
Stopband width @-30dB	22.4 nm
Transmission variation in Passband	0.12 dB
Substrate size	Ø 150 mm
Substrate thickness	10 mm

w/o Backside Coating





# THANK YOU FOR YOUR ATTENTION!

FOR MORE INFORMATION AND INQUIRIES PLEASE CONTACT: [ANTUN.PEIC@SOLAYER.COM](mailto:ANTUN.PEIC@SOLAYER.COM)